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Information Disclosure Statement By Applicant	Applicant: Han et al.	
(Use Several Sheets if Necessary)	Filing Date 1/28/02	Group 2862 2829

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
VN	A1	T. P. Chang et al., "Arrayed miniature electron beam columns for high throughput sub-100 nm lithography", J. Vac. Sci. Technol. B, Vol. 10, No. 6, Nov./Dec. 1992, pp. 2743-2747.
VN	A2	E. Yin et al., "Electron optical column for a multicolumn, multibeam direct-write electron beam lithography system", J. Vac. Sci. Technol. B, Vol. 18, No. 6, Nov./Dec. 2000, pp.3126-3131.
VN	A3	T. R. Groves et al., "Distributed, multiple variable shaped electron beam column for high throughput maskless lithography", J. Vac. Sci. Technol. B, Vol. 16, No. 6, Nov./Dec. 1998, pp. 3168-3173.
Examiner <i>smk Nguye</i>		Date Considered <i>03/19/04</i>

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.